

Notice of References Cited	Application/Control No. 10/718,381	Applicant(s)/Patent Under Reexamination KERMEL ET AL.	
	Examiner Walter L. Lindsay, Jr.	Art Unit 2812	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,290,859	09-2001	Fleming et al.	438/704
	B	US-6,156,126	12-2000	Chen et al.	438/748
	C	US-6,221,766	04-2001	Wasserman, Yuval	438/656
	D	US-6,664,196	12-2003	Wada et al.	438/754
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Derwent-ACC-No. 2002-178025, Kim, D. H. et al. Gate electrode manufacture of semiconductor device including cleaning with mixture of sulphuric acid and hydrogen peroxide, 12/30/1999. KR-0067263
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.